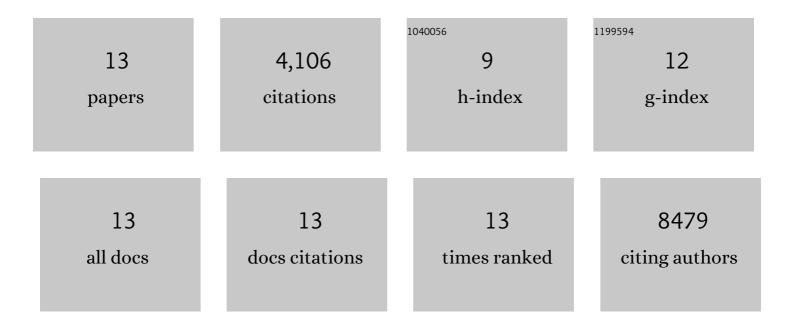
## Tero S Kulmala

List of Publications by Year in descending order

Source: https://exaly.com/author-pdf/6119053/publications.pdf Version: 2024-02-01



#	Article	IF	CITATIONS
1	Quantifying Defects in Graphene via Raman Spectroscopy at Different Excitation Energies. Nano Letters, 2011, 11, 3190-3196.	9.1	2,807
2	Inkjet-Printed Graphene Electronics. ACS Nano, 2012, 6, 2992-3006.	14.6	1,018
3	Ultrafast and widely tuneable vertical-external-cavity surface-emitting laser, mode-locked by a graphene-integrated distributed Bragg reflector. Optics Express, 2013, 21, 31548.	3.4	111
4	Carbon nanotube thin film transistors based on aerosol methods. Nanotechnology, 2009, 20, 085201.	2.6	45
5	Platinum and palladium oxalates: positive-tone extreme ultraviolet resists. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2015, 14, 043511.	0.9	35
6	SnOx high-efficiency EUV interference lithography gratings towards the ultimate resolution in photolithography. Microelectronic Engineering, 2016, 155, 44-49.	2.4	34
7	Novel carbon nanotube network deposition technique for electronic device fabrication. Physica Status Solidi (B): Basic Research, 2008, 245, 2272-2275.	1.5	14
8	Self-Aligned Coupled Nanowire Transistor. ACS Nano, 2011, 5, 6910-6915.	14.6	12
9	EUV lithography process challenges. Frontiers of Nanoscience, 2016, 11, 135-176.	0.6	9
10	Toward 10Ânm half-pitch in extreme ultraviolet lithography: results on resist screening and pattern collapse mitigation techniques. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2015, 14, 033507.	0.9	8
11	Toward 10nm half-pitch in EUV lithography: results on resist screening and pattern collapse mitigation techniques. Proceedings of SPIE, 2015, , .	0.8	7
12	Pattern collapse mitigation in inorganic resists via a polymer freeze technique. Microelectronic Engineering, 2016, 155, 39-43.	2.4	6
13	A bottom-up pattern collapse mitigation strategy for EUV lithography. Proceedings of SPIE, 2016, , .	0.8	0